

IN THE SPECIFICATION:

Please AMEND the specification as follows:

Please substitute the paragraph beginning at page 2, line 15, with the following.

-- In contrast, a multi-beam system which draws patterns at the same time with a plurality of electron beams without using any mask is proposed. This system eliminates the need to manufacture a physical mask, set the mask in an exposure apparatus, and replace the mask. Accordingly, the system can be put into practical use with many advantages. For example, a multi-electron beam exposure apparatus for drawing patterns by using a plurality of electron beams is described in "Hiroshi Yasuda: Applied Physics ~~69~~ 63, 1135 (1994)". --